

ABSTRACT OF THE DISCLOSURE

RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN

5 a resist composition which generates acid upon exposure and exhibits changed solubility in a developing solution under action of acid, the resist composition including a base component (A) which exhibits changed solubility in a developing solution under action of acid, and an ion liquid (Z), wherein a solid content of the resist composition is 25% by weight or more.

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Figure for publication: None